SUSS MicroTec Lithography GmbH

Schleissheimer Str. 90 · D-85748 Garching b. München · Germany Phone (+49)-(0) 89/3 20 07-0 · Fax (+49)-(0) 89/3 20 07-162

SUSS MicroTec Test Systems GmbH

Süss-Strasse 1 · D-01561 Sacka b. Dresden · Germany Phone (+49)-(0) 35240-73-0 · Fax (+49)-(0) 35240-73-700

SUSS MicroTec S.A.

Avenue des Colombières \cdot F-74490 Saint Jeoire \cdot France Phone (+33)-(0) 4 50 35 83 92 \cdot Fax (+33)-(0) 4 50 35 88 01

SUSS MicroTec Laboratory Equipment GmbH

Josef-Schuettler-Str. 2 · D-78224 Singen · Germany Phone (+49)-(0) 7731-185-0 · Fax (+49)-(0) 7731-195-130

SUSS MicroTec Ltd.

Hogwood Ind. Estate, 23, Ivanhoe Road Finchampstead, Wokingham, Berkshire RG40 4QQ, England Phone (+44)-(0) 1189-732144 · Fax (+44)-(0) 1189-734395

NORTH AMERICA

SUSS MicroTec Inc.

228 Suss Drive · Waterbury Center, VT 05677 · USA Phone (802) 244-5181 · Fax (802) 244-5103

SUSS MicroTec Inc.

Wester Regional Sales Offive, 8240 So. Kyrene Road Suite 101 Tempe, AZ 85284-2117 Phone (+1) (480) 557-9370 · Fax (+1) (480) 557-9371

ASIA

SUSS MicroTec Company Ltd.

3388/92-93 · 25th Floor · Sirinrat Bldg.
Rama IV Road · Klongtoey · Bangkok 10110 · Thailand
Phone (+66)-(0) - 2350 6038 · Fax (+66)-(0) -2633 5728

SUSS MicroTec AG

Taiwan Representative Office 8F-11, 13 · No. 81 · Shui-Lee Road ·

8F-11, 13 · No. 81 · Shui-Lee Road · Hsin-Chu · 300 · Taiwan Phone (+886)-(3) 5169098 · Fax (+886)-(3) 5169262

SUSS MicroTec AG

Shanghai Office

580 Nanjing W. Rd · Nanzheng Building Room 606 · 200041 Shanghai Phone (+86) 21-52340432 · Fax (+86) 21-52340430

JAPAN

SUSS MicroTec KK

ズース・マイクロテック株式会社

〒226-0006 神奈川県横浜市緑区白山1-18-2 ジャーマン・インダストリー&トレード・センター

GITC 1-18-2, Hakusan, Midori-ku, Yokohama, Kanagawa, Japan 226-0006 Phone (+81)-45-931-5600 · Fax (+81)-45-931-5601 Subject to change without prior notice



SPIN COATERS



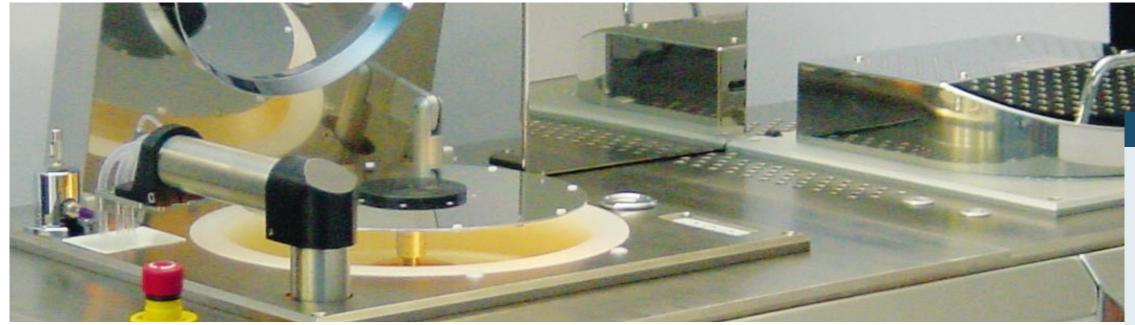






Chip Bonders

Mask Aligners





Universal 8" Coating System / Advanced Spin Coating

The **DELTA 80** is the newest SUSS Spin Coater based on the well known SUSS patented GYRSET® closed cover coating technology. It combines state of the art technology with innovative excellence. The **DELTA 80** can process delicate wafer fragments, wafers up to Ø 8" (Ø 200 mm) or substrates up to 6" x 6" (150 x 150 mm).

The unique design of the **DELTA 80** process chamber provides a better uniformity than conventional open bowl spin coaters. At the same time it can significantly reduce resist consumption up to 60% for resists like Cyclotene[™] (BCB) compared to conventional Spin Coating systems. The Delta 80 is also the ideal tool for coatings over high topography

Better uniformity and less resist consumption make the SUSS **DELTA 80** Spin Coater the ideal tool regarding the cost of ownership.

The SUSS **DELTA 80** Spin Coater is simple to operate with fully programmable process parameters. The system is available as a bench mounted module (BM) or for stand alone (T version) operation integrated into an attractive stainless steel cabinet. A variety of options are available.





- Uniform coatings with the SUSS patented GYRSET® technology, reduced resist consumption and less edge build-up are the guarantee for very high quality process and repeatability, especially on square or rectangular substrates
- Multi size configuration with automatic GYRSET® cover size detection and spin speed limitation set up provide the flexibility to meet all major application types
- GYRSET® quick exchange system, allows for easy change over between wafer sizes.
- The process bowl made of polypropylene is easily removed for cleaning the process chamber
- Wafer size up to Ø 8" (Ø 200mm) and substrates up to 6" x 6" (150 x 150mm)
- Spin speed from 1 up to 10.000 rpm (depends on GYRSET® size or Open Bowl option)
- Fully programmable process parameters with easy to use keyboard and clear text display
- Storage of 20 recipes with up to 40 steps at each recipe or **unlimited** numbers of recipes storable with laptop option
- For the programmable dispense arm different resist pumps, syringe systems and media nozzles for accurate and precise dispense are available
- Modular design, the ability to mount the modules into a wet bench or a stand alone stainless steel cabinet
- Chuck indexing for positioning the chuck accurately at the same position for easy load / unload



Benefits Of Ownership

THE PATENTED SOLUTION

The SUSS EITH 80 Is Capable Of Processing:

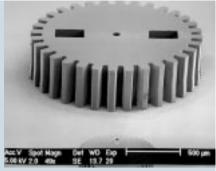
- Si and GaAs wafers and substrates
- Polyimide/SOG/adhesive promoters
- Microsystem technology
- Rectangular substrates
- Flat panel display (passive, active, plasma, FED)
- Positive/negative photoresist
- Concave and convex lenses
- Photomasks
- Photocells
- Compact disks (ROM, audio, video)
- Glass mastering with thin layer coating
- Optical lenses, encoders, scales
- X-ray masks
- Bumping applications for flip chip

THE GYRSET® SYSTEM

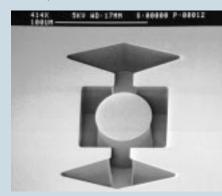
The patented SUSS GYRSET® system is based on a simple but revolutionary concept. Compared to a conventional spin coating system it has multiple unparalleled advantages. The GYRSET® system offers better uniformity and up to 60% resist cost saving (depending on resist).

The GYRSET® system with indexed bell-shaped cover excludes air turbulence inside the process chamber. This technique yields a uniform, consistent coating thickness without the usual spinning defects (no rebounding, no splashback, no striations, no comets, no corner effects).

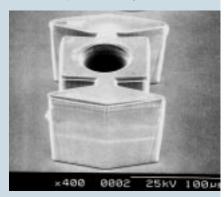
Because of the solvent-saturated atmosphere inside the process chamber, less resist dry skin effect occurs. Consequently, better uniformity and process control for thick as well as for thin resist layers are produced.



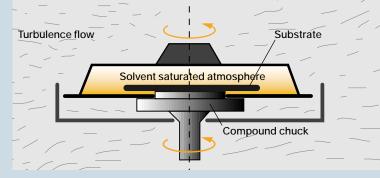
Photoplastic gear, 450 µm high SU-8 resist Courtesy: SFIT (EPFL) and IBM (CH)



Photoresist pattern of 57 µm thickness



NiFe rotor element, 85 µm high, single shot coating

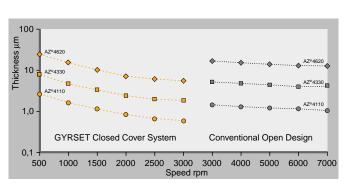


GYRSET® system design

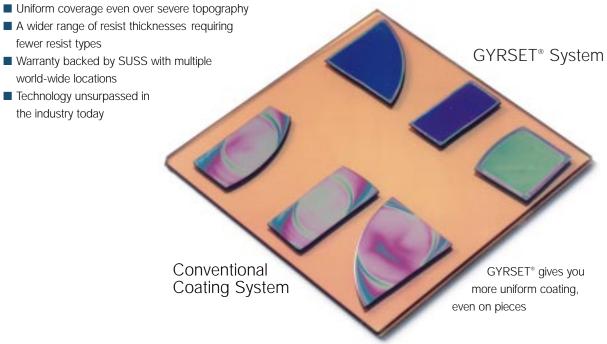
BENEFITS OF OWNERSHIP

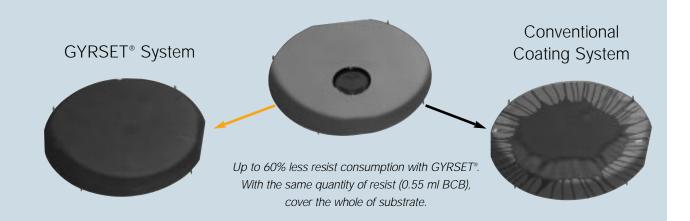
SUSS GYRSET® A Wise Investment

- Reliable, consistent and uniform material application at lower spin speeds
- Economic ownership costs including lower resist consumption and reduced waste disposal expenses
- Service that is a cornerstone of our products and our reputation in the industry
- Highly reproducible thick resist applications
- A wider range of resist thicknesses requiring fewer resist types
- Warranty backed by SUSS with multiple world-wide locations
- Technology unsurpassed in the industry today



GYRSET® offers an order of magnitude wider range at lower spin speeds



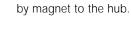


Multi-Size GYRSET®

Choose between a fixed or quick exchange

 $\mathsf{GYRSET}^{\circledR}$ plate. Easily removable for cleaning, the

quick exchange $\mathsf{GYRSET}^{(\! R \!)}$ plate is simply locked





Delta 80 GYRSET 3

7 000 rpm

5 000 rpm

Delta 80 GYRSET 8

Interchangeable GYRSET® Systems for 2" up to 8" parts

SIMPLE AND FLEXIBLE

The **DELTA 80** can be equipped with three different GYRSET® sizes: 2" up to 8". The configuration is automatically detected and the maximum speed set

accordingly. With a change over time of less than 5 minutes, the SUSS **DELTA 80** GYRSET[®] is the most





8" Quick Exchange GYRSET®

5" high profile and 5" standard profile GYRSETS

Select the GYRSET® height according to the thick-

ness of your substrate. Use the table below to help

Maximum Substrate Maximum Spin

Speed (rpm)

3 000

5 000

7 000

Thickness (mm)

Maximum Substrate

Thickness (mm)

Maximum Spin

Speed (rpm)

3 000

3 000

3 000

Multi-Profile GYRSETS

you choose the correct size.

Delta 80 GYRSET 8

Delta 80 GYRSET 5

Delta 80 GYRSET 3

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MODULAR OPTIONS

The **DELTA 80** can be configured with two different dispense arms, either fully programmable electronic dispense or pneumatic driven dispense arm.

The programmable electronic dispense arm provides more flexibility. It is fully programmable in speed, acceleration and position and can be equip-

ped with up to 6 media lines - maximum 4 resist lines and 2 solvent lines. It is also possible to fit the edge bead remover, nitrogen blow or bowl auto-

The pneumatic dispense arm can be equipped with

only one resist line and has only two positions,

Dispense Arms (Options)

clean option.

home and dispense position.

SIMPLE AND FLEXIBLE

Choose either double or single side chucks in 8", 2" or smaller sizes. The substrates are vacuum-locked during processing. The vacuum patterns, support pins and locating pins are designed according to your components and adapted to the options chosen.

Available for single side chucks, these adapters allow you to process pieces up to 2" on a larger size chuck.

3" Double Side Chuck

3" Single Side Chuck

3" Single Side Chuck with Adapter

Double Side (LC)* And

Adapters For Small Pieces

*Low Contact

Single Side Chucks









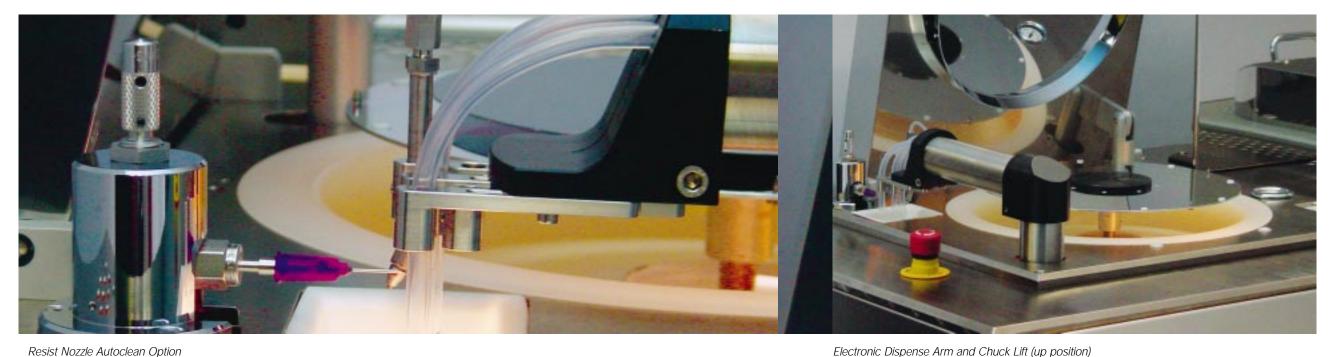












Resist Nozzle Autoclean Option

This fully programmable option removes the resist build-up at the edge of the wafer. All tubing valves and flowmeters are included. Wafers up to 8" (200mm) in diameter can be processed.

Edge Bead Remover (Options)

Solvent Dispense Nozzle (Options)

Choose this programmable option for solvent cleaning or developing and for adhesion promoter dispense. It includes all tubing, valve and flowmeter.

Nitrogen Blow (Options)

Releases a jet of nitrogen across your wafer / substrate before processing and helps to remove any dust and dirt particles from the surface, thereby cleaning the component. Includes all tubing, valve and flowmeter.

This programmable solvent nozzle dispenses solvent onto the GYRSET® cover to remove stringers (cotton candy). It also cleans the process chamber before the process stops.

Cotton Candy Remover (Options)

It provides excellent results and reduces substrate contamination due to cotton candy effects.

Bowl Auto Clean (Options)

Programmable cleaning cycle cleans the chuck and the process bowl. The auto-cleaning frequency can be set either by time or numbers of cycles.

Resist Nozzle Auto Clean (Options)

This fully programmable option injects solvent onto the required dispense nozzle dissolving any residue and cleaning the inside of the nozzle.

Dispense Systems (Options)

Different high and low viscosity photo resist pumps are available. For more flexibility a programmable syringe dispense system is available.

Open Bowl (Options)

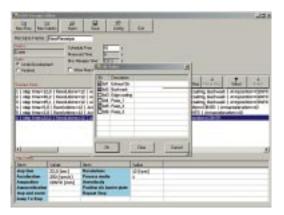
The open bowl option with the special sensor controlled adapter ring allows for conventional open bowl spin coating. The adapter permits speeds up to 10,000 rpm without GYRSET® cover and provides additional flexibility to process wafers or substrates.

Chuck Lift (Options)

Allows easy loading and unloading of the wafer combined with the standard chuck indexing for repeatable wafer positioning.

Laptop (Options)

The laptop option with a Windows® like user interface software allows for easy recipe programming and storage for an unlimited number of recipes.



Laptop Option



Stainless Steel Cabinet

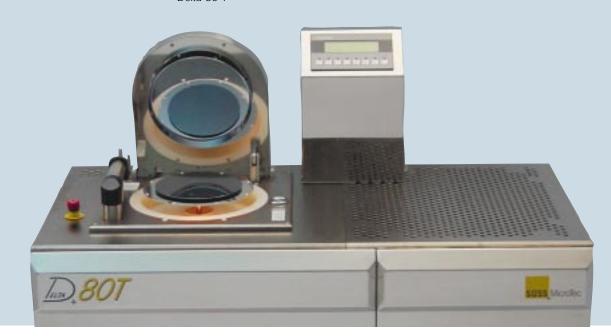
The stand alone cabinet integrates the SUSS DELTA 80 Spin Coater with selected options, like our DELTA 150 / 200 BM Hotplate Modules into a small footprint. The top plate with the front panels of the cabinet are made of polished stainless steel. Side and back panels are made of brushed stainless steel and are easily removed allowing easy access to all components.

The perforated top plate provides a laminar flow assuring proper ventilation through the process. For added safety and reduced contamination the media and electronic controller are seperated. All connections for media and power are located on the back of the cabinet simplifying installation.

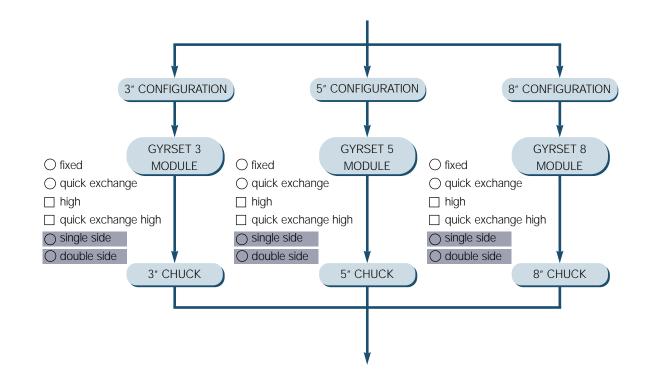
Special Requirements

If you have special requirements, the SUSS team will help you to define and support your particular need, whether for research or production.

Delta 80 T



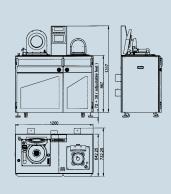
DELTA 80 GYRSET®



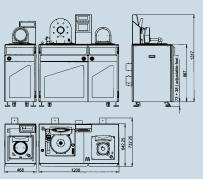
Options				
Stainless steel cabinet	Nitrogen blow			
Programmable electronic dispense arm Pneumatic dispense arm Programmable solvent dispense	Dispense pumps			
	Chuck lift-up / down			
	Adapter for small substrates, up to 2"			
	Laptop			
Resist nozzle autoclean	Motor flange cooling			
Programmable bowl autoclean	Open bowl spinning			
Edge bead remover	Pressure vessel systems + Media cabinet			
Cotton candy remover	Media filter systems			

	-Drain 5
Scree DIN 912 MG (4x)	

DELTA 80 BM	
Requirements	
Voltage:	230 VAC / 50 Hz / 16 A
Compressed air:	5 - 6 bar / tube OD 8 mm
Vacuum:	min 0.7 bar / tube OD 6 mm
Nitrogen:	4.5 bar / tube OD 6 mm
Exhaust:	OD 100 mm (1x)
Dimensions	
Spinner module (W x D x H):	443 x 440 x 830* (17.4" x 17.3" x 32.7"*)
	*with open GYRSET® cover and waste bottle
Controller (W x D x H):	465 x 386 x 133 mm (18.3" x 15.2" x 5.2")
Panel interface (W x D x H):	196 x 56 x 110 mm (4.3" x 7.7" x 2.2")



DELTA 80 T + T2 Requirements	
Voltage:	400 VAC / 50 Hz / 16 A
Compressed air:	5 - 6 bar / tube OD 8 mm
Vacuum:	min 0.7 bar / tube OD 8 mm
Nitrogen:	4.5 bar / tube OD 8 mm
Exhaust:	OD 100 mm (3x)
Dimensions	
Footprint (W x D x H):	1200 x 642 x 1317 mm (47.2" x 25.3" x 51.9")



DELTA 80 T3 Requirements	
Voltage:	400 VAC / 50 Hz / 16 A
Compressed air:	5 - 6 bar / tube OD 8 mm
Vacuum:	min 0.7 bar / tube OD 8 mm
Nitrogen:	4.5 bar / tube OD 8 mm
Exhaust:	OD 100 mm (3x)
Dimensions	
Footprint (W x D x H):	1674 x 642 x 1317 mm (65.9" x 25.3" x 51.9")

Data depend on individual process conditions and can vary according to equipment configurations. Not all specifications may be valid simultaneously. Illustrations in this brochure are not legally binding. Design and specification of custom built machines depend on individual conditions and can vary according to equipment configurations.



Semiautomated Process Equipment

The SUSS Delta Series offers a wide range of laboratory equipment that can process wafers or substrates ranging from pieces up to 22" diameter or 16" square. The Delta Series includes process modules for the following applications:

- Substrate Dryers
- Coating Systems
- Hot Plates
- Cool Plates
- Develop and Etching Systems
- Cleaning Systems
- Vapor Priming (HMDS)



For stand alone operation the Delta Series modules can be integrated into attractive stainless steel cabinets. The cabinets can support from one up to three different process modules. For example, it is possible to have a coater, vapor prime and hot plate module located in a single cabinet. The modular design allows our customers a great deal of flexibility configuring process equipment while minimizing space.

Technical Data